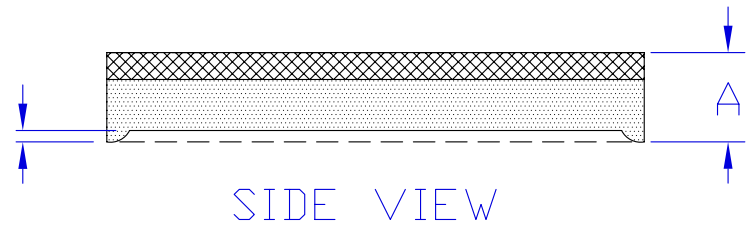


SUBSTRATE MATERIAL

| D | D3 | Dwg Nbr | Dwg Nbr |
|----|----|---------|---------|
| E | E3 | BT | RO4003C |
| 2 | 1 | 202000 | 202040 |
| 3 | 2 | 203000 | 203040 |
| 4 | 3 | 204000 | 204040 |
| 5 | 4 | 205000 | 205040 |
| 6 | 5 | 206000 | 206040 |
| 7 | 6 | 207000 | 207040 |
| 8 | 7 | 208000 | 208040 |
| 9 | 8 | 209000 | 209040 |
| 10 | 9 | 211000 | 211040 |
| 12 | 11 | 212000 | 212040 |

Cavity wall
variance
0.05~0.15



HEIGHT TABLE

| SERIES | C1 | C2 | A |
|---------|----------|----------|----------|
| A-CAP | 0.63 | 0.27 | 0.90 |
| A-TCAP | 0.38 | 0.27 | 0.65 |
| TOL +/- | +/- 0.10 | +/- 0.05 | +/- 0.15 |

OTHER SIZES AVAILABLE

Notes:

- Organic substrate
- Pin 1 indicator pad: Cu/Ni/Au
- Cavity dam: Hysol FP4451TD
- Dimensions are mm

THIS DOCUMENT AND THE TECHNOLOGY IT REPRESENT ARE, AND SHALL REMAIN, THE PROPRIETARY PROPERTY OF MIRROR SEMICONDUCTOR. THIS DOCUMENT IS PROVIDED TO RECIPIENT ON A CONFIDENTIAL BASIS WITH THE RECIPIENT'S AGREEMENT THAT IT WILL NOT REPRODUCE, COPY, LOAN, EXHIBIT NOR USE, EITHER IN WHOLE OR IN PART, THE DOCUMENT OR ITS CONTENT, EXCEPT IN THE LIMITED WAY AND FOR ITS PRIVATE USE AS PERMITTED BY MIRROR SEMICONDUCTOR.

| | | | | | | |
|--|---|------------------|---------------------------|-------|--|--|
| TOLERANCES UNLESS NOTED: X.XX ± X.XXX ± X.XXXX ± ANGLES ± | APPROVALS DRAW TA ENG MFG QA CUST REVISED | DATE 03/15/09 | | | | |
| ALL DIMENSIONS ARE IN: <input type="checkbox"/> INCHES <input type="checkbox"/> MILLIMETERS | THIRD ANGLE PROJECTION: | | TITLE A-CAP (DOME LID) | | | |
| SCALE NONE | | SIZE A | DRAWING NO. 200000 | REV A | | |
| DO NOT SCALE DRAWING | | | SHEET 1 OF 1 | | | |